

Objective lenses for mask / wafer inspection

Features

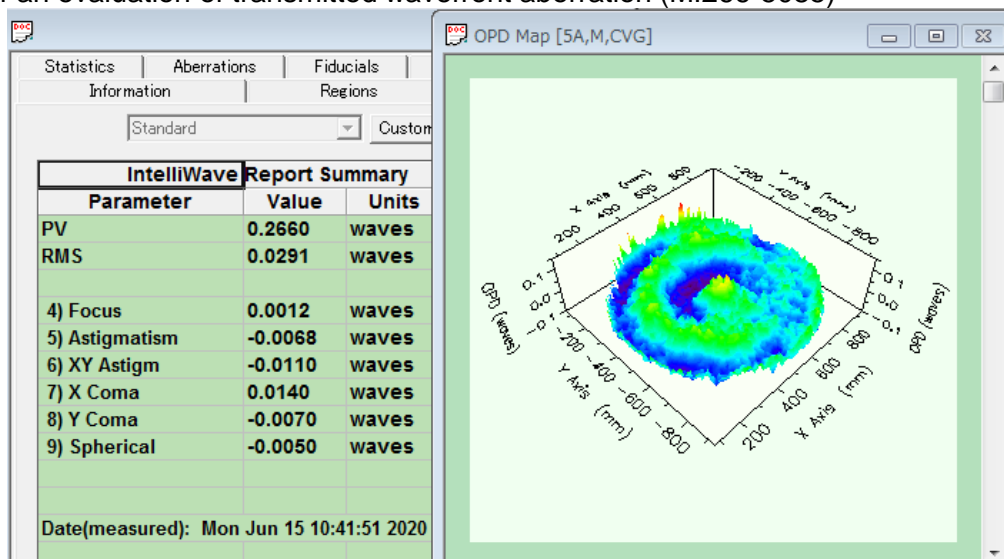
- ◎ From its refractive optical system, it has no shielding and long working distance.
- ◎ It is achromatic within the spectrum of the laser, resulting in good imaging properties.
- ◎ The design performance is numerically guaranteed by measuring wavefront aberration with an interferometer.
- ◎ Suitable for semiconductor mask / wafer observation applications.



The MI series of objective lenses for mask / wafer inspection have co-functioning with a wide field of view, long working distance, and aberration-free, that results in high suitability for semiconductor photomask / wafer inspection.

Custom arrangement is available for the interface part and various relay lenses.

- Sample for an evaluation of transmitted wavefront aberration (MI266-5085)



Optical components, optical systems, lasers



KYOCERA SOC Corporation

Contact us:

TEL: +81-45-931-6592

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Responsible for sales: Kobayashi and Kimura

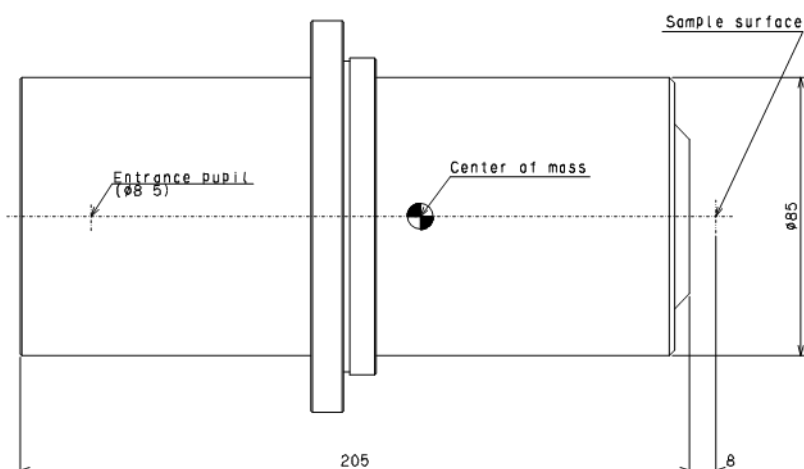
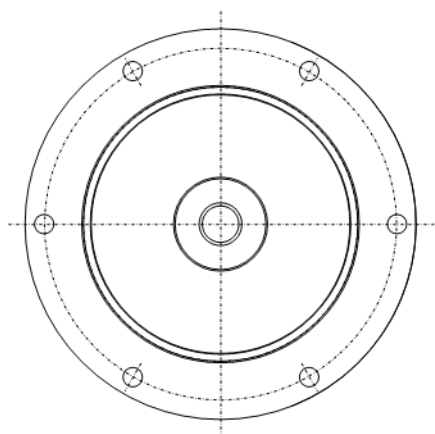


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● Lineup

Model name	MI193-5085	MI213-5085	MI248-5085	MI266-5085	MI355-5085
Wavelength	193nm	213nm	248nm	266nm	355nm
Bandwidth (full width at half maximum)	10pm	15pm	20pm	30pm	100pm
Type	Refractive type				
Numerical aperture (NA)	0.85				
Focal length	5mm				
Transmittance	80% or more				
Field of view	φ0.45mm				
Wavefront aberration	≤ 0.03 waves rms				
Working distance	≥ 8mm				
Dimensions	φ85mm × L205mm (excluding flanged part)				
Mass	Approx. 4250g				

● External Dimensions



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